## **ABSTRACT**

The present invention relates to a method of depositing a crystalline  $\alpha$ -Al<sub>2</sub>O<sub>3</sub>-layer onto a cutting tool insert by Chemical Vapor Deposition at a temperature of from about 625 to about 800 °C. The method comprises the following steps:

depositing a from about 0.1 to about 1.5  $\mu$ m layer of TiC<sub>X</sub>N<sub>y</sub>O<sub>Z</sub> where x+y+z>=1 and z>0, preferably z>0.2;

treating said layer at 625-1000 °C in a gas mixture containing from about 0.5 to about 3 vol-%  $O_2$ , preferably as  $CO_2 + H_2$  or  $O_2 + H_2$ , for a short period of time from about 0.5 to about 4 min, optionally in the presence of from about 0.5 to about 6 vol-% HCl; and

depositing said Al<sub>2</sub>O<sub>3</sub>-layer by bringing said treated layer into contact with a gas mixture containing from about 2 to about 10 vol-% of AlCl<sub>3</sub>, from about 16 to about 40 vol-% of CO<sub>2</sub>, in H<sub>2</sub> and 0.8-2 vol-% of a sulphur-containing agent, preferably H<sub>2</sub>S, at a process pressure of from about 40 to about 300 mbar. The invention also includes a cutting tool insert with a coating including at least one  $\alpha$ -Al<sub>2</sub>O<sub>3</sub>-layer according to the invention.